



**SEAL SP13 – MCEB
HIGH RESOLUTION MULTI
COLUMN E-BEAM WAFER
INSPECTION – PROTOTYPE
ASSESSMENT AT WAFER FAB
PRODUCTION FLOOR**

AT A GLANCE

- Assessment of E-Beam inspection technology meeting resolution and throughput requirements of 22nm node
- Tool improvements based on fab feedback

SEAL SP13 – PARTNERS

Applied Materials
Global Foundries
IC Testing

Advances in PLASMA-TRANS

- A high resolution E-Beam defect inspection tool for the 22nm node and below
- Production worthy throughput will be reached with a Multi Column E-Beam inspection tool.
- High resolution is targeted having the required sensitivity for high capture rate defect detection and will be evaluated for defect monitoring in critical layers

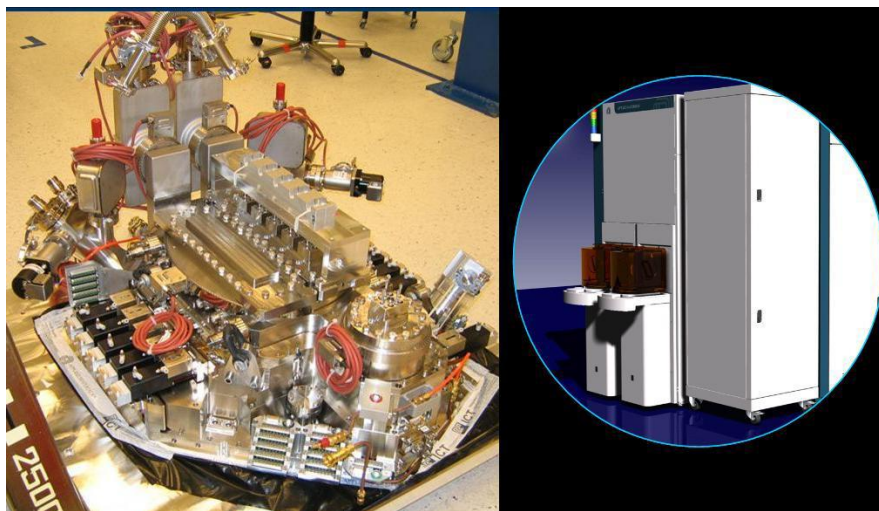


FIGURE 1: THE ELITE MULTI COLUMN E-BEAM INSPECTION TOOL (RIGHT) AND THE MULTI COLUMN MODULE (LEFT)



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SEAL PROJECT – BULLETIN

SEAL SP13 – MCEB HIGH RESOLUTION MULTI COLUMN E-BEAM WAFER INSPECTION – PROTOTYPE ASSESS- MENT AT WAFER FAB PRODUCTION FLOOR

SEAL PROJECT MANAGEMENT

Prof. Lothar Pfitzner
Fraunhofer IISB
Schottkystraße 10
D-91058 Erlangen
T: +49(0)9131/761-110
I: www.iisb.fraunhofer.de

Project Results

AMIL and ICT developed a Multi-Column E-Beam inspection technology that will meet resolution and throughput requirements of 22nm technology. A prototype tool is installed in production environment at Global Foundries Production Fab and full assessment has been done by a team of the sub project in two phases. In between the phases, an upgrade was done to the tool according to GF feedback. The goal of the sub project were a report and publication on the readiness of the technology for HVM.

SP8 – CONTACT

Yoram Uziel

AMIL

I: www.appliedmaterials.com

SEAL WEBSITE

www.seal-project.eu



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